

1752



Attorney Docket No.: Q60118
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

MIZUTANI, KAZUYOSHI, et al.

Appln. No.: 09/615,708

Group Art Unit: 1752

Filed: July 13, 2000

Examiner: C. Hamilton

For: BOTTOM ANTI-REFLECTIVE COATING MATERIAL COMPOSITION AND
METHOD FOR FORMING RESIST PATTERN USING THE SAME

AMENDMENT AND RESPONSE

Commissioner for Patents
Washington, D.C. 20231

Sir:

This Amendment and Response are to the Office Action mailed March 7, 2001. The Examiner set a one month period for response, making this response due on or before Monday, April 9, 2001.

Please amend the application as follows:

IN THE CLAIMS:

Claim 24 (amended):

A method for forming a resist pattern, comprising the steps of:

dissolving a bottom anti-reflective coating material composition of claim 12 in a solvent to provide a bottom anti-reflective coating solution;
coating the bottom anti-reflective coating solution on a substrate to form a bottom anti-reflective coating;

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